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## The Dynamic Spectroscopic Ellipsometry(SE) Data for Aluminum Thin Films Oxidations

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## **The Dynamic Spectroscopic Ellipsometry(SE) Data for Aluminum Thin Films Oxidations**

Keywords: Dynamic SE, Aluminum mirror coating, Oxidation

The dynamic spectroscopic ellipsometry (SE) data captured on oxidation of ultra thin evaporated aluminum film over starting a few minutes after evaporation and continued for four hours. The Aluminum layer was ca. 15 nm thick. This data needs to be interpreted with J.A. Woollam CompleteEase software. The Aluminum was modeled with Lorentz model and the Alumina was modeled using Cody-Lorentz.